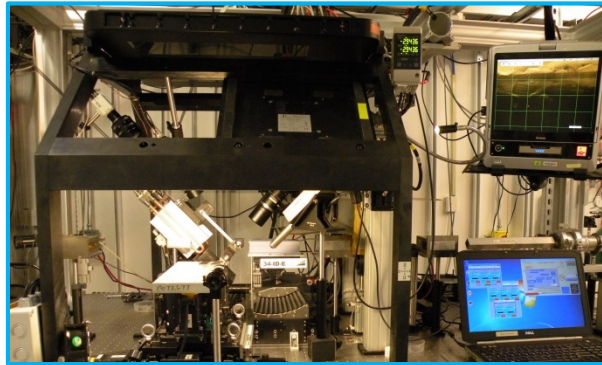


X-ray Laue Diffraction Microscopy in 3D (34-ID-E, APS)

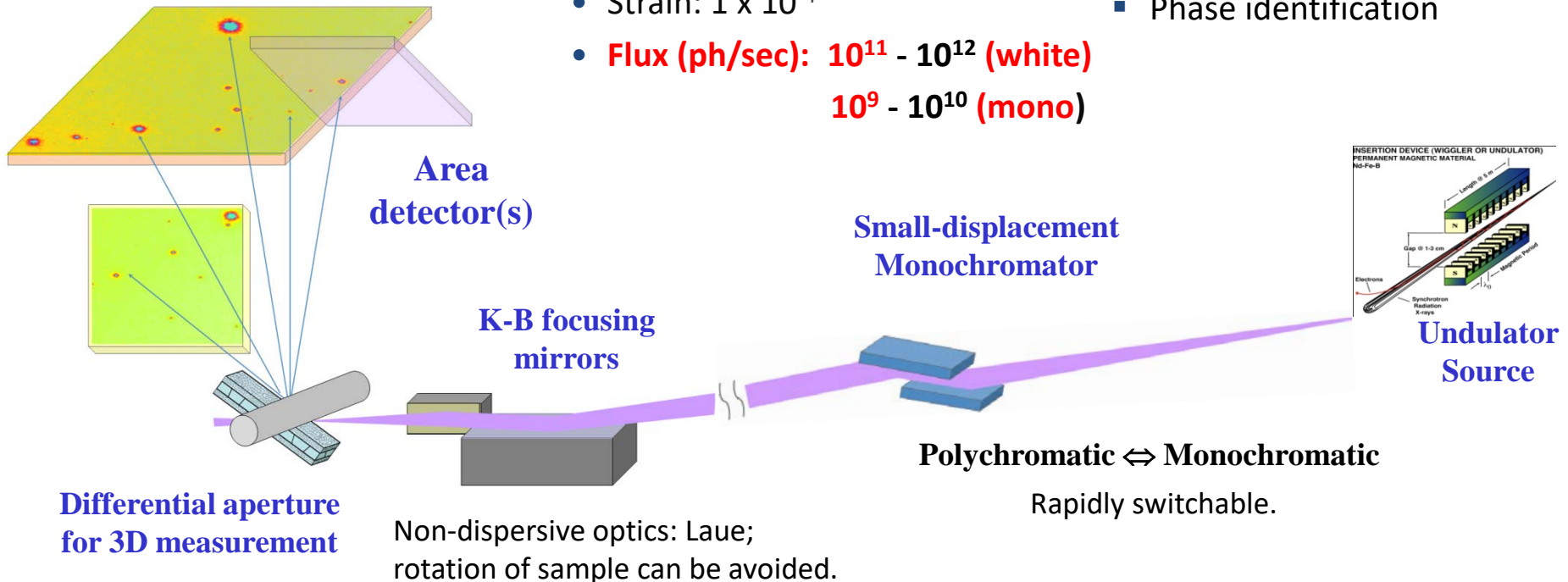


Routine operation:

- Energy range: 7 - 30 keV
- Resolutions:
 - **Spatial: $0.2 \times 0.3 \times 1.0 \mu\text{m}^3$**
used to be **$0.5 \times 0.5 \times 1.0 \mu\text{m}^3$**
 - Angular: 0.01°
 - Strain: 1×10^{-4}
 - **Flux (ph/sec): $10^{11} - 10^{12}$ (white)**
 $10^9 - 10^{10}$ (mono)

Measure:

- Crystallographic orientation
- Orientation gradients
- Strain tensor
- Phase identification

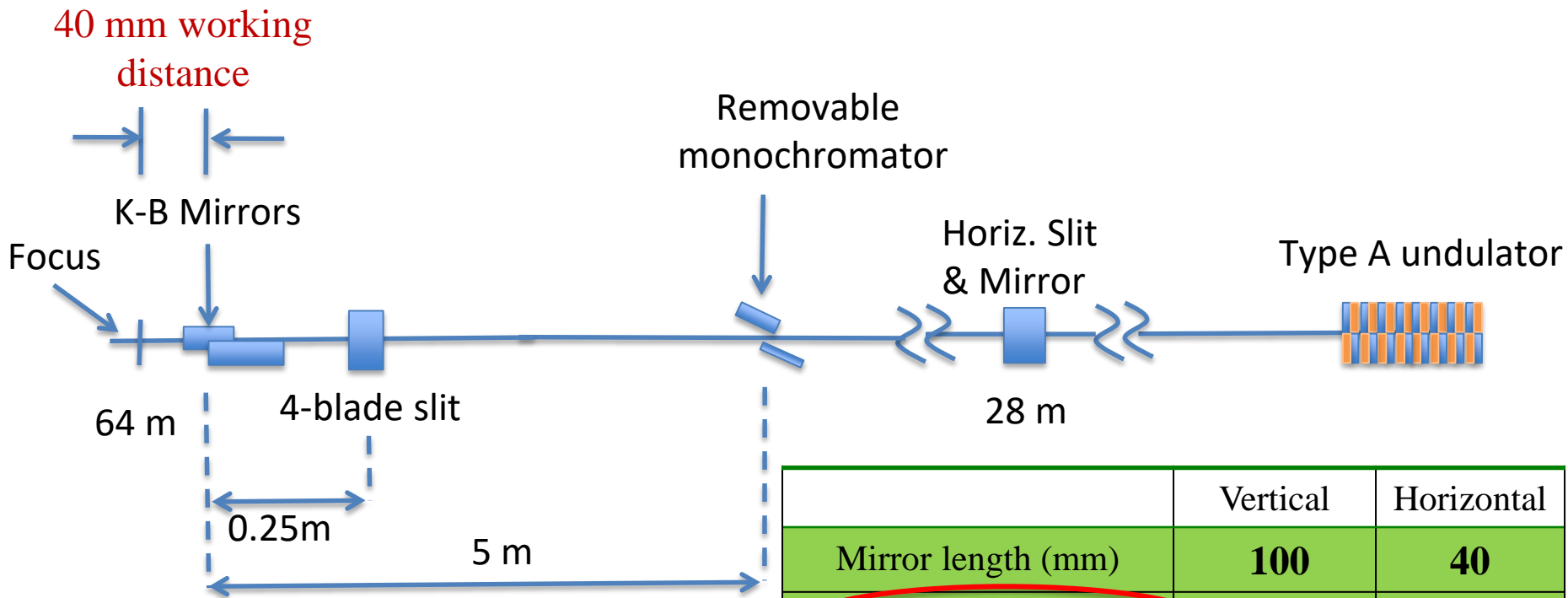


Outline of Facility

- Two instruments (in one larger hutch), currently plan to remain at 34-ID
- Upstream instrument provides 3D diffraction with spots in the <200 nm range, larger working distance, and some coherent diffraction.
- Downstream instrument provides 3D diffraction from spots ~ 50 nm in size. With extra-special temperature stabilization.



34-ID-E Micro-diffraction Beamline Focusing Optics



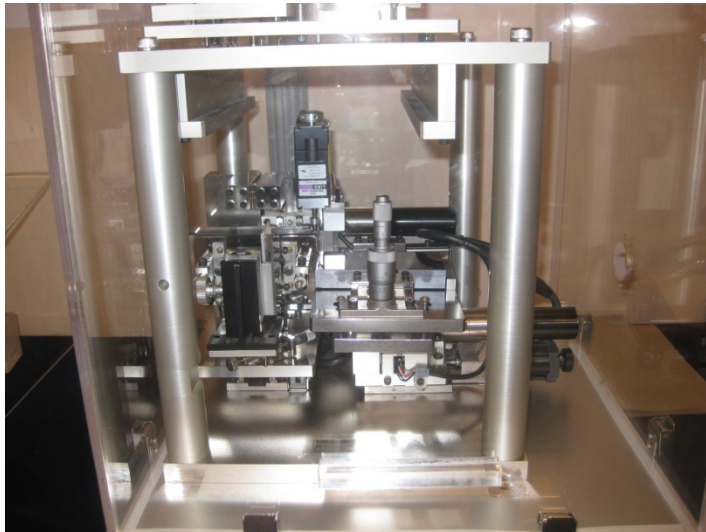
**Mirror box: in UHV;
Used to be helium gas protected**

Conventional (~ 64 m long) beamline
at 3rd generation synchrotron

* Pt coated

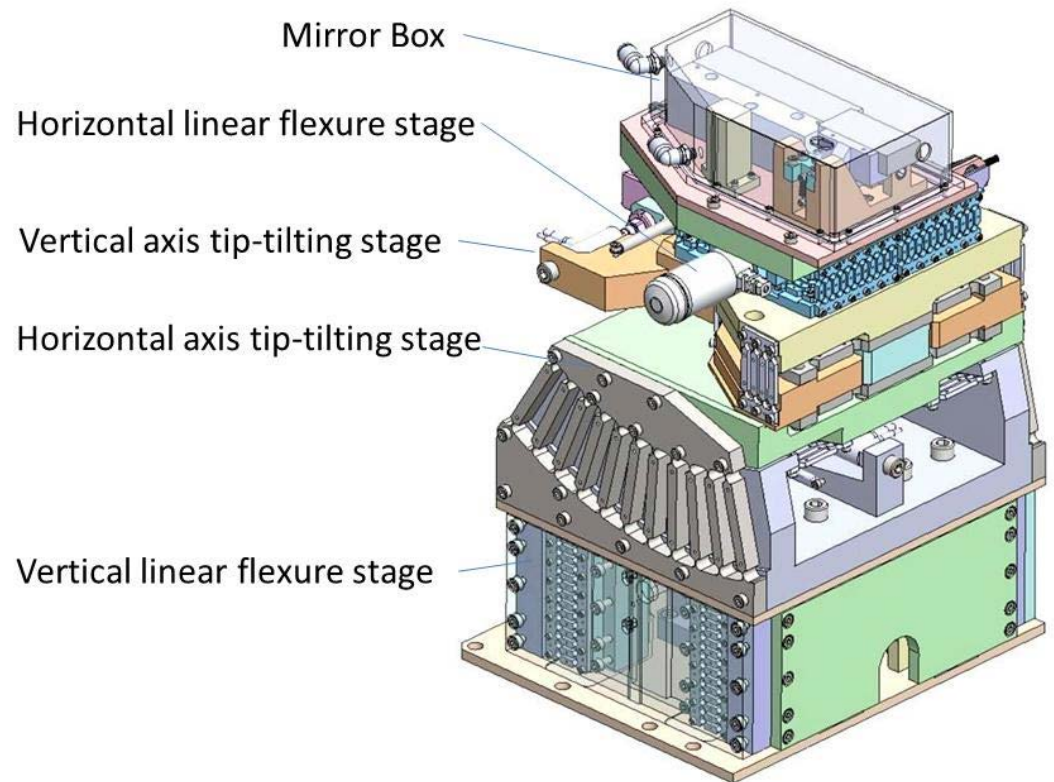
	Vertical	Horizontal
Mirror length (mm)	100	40
Focal length (mm)	132	60
Geometrical demag.	490	600
Glancing angle (mrad)	3.0	3.0
Max. beam accept. (μm)	270	100
Max. NA (mrad)	1.02	0.83
Energy cut-off * (keV)	28	

Mirror control



JTEC Mirror Positioning unit
(JM-1000)
USD ~ \$200K

Want 100 nr rms for large spot
& 50 nr rms for small spot



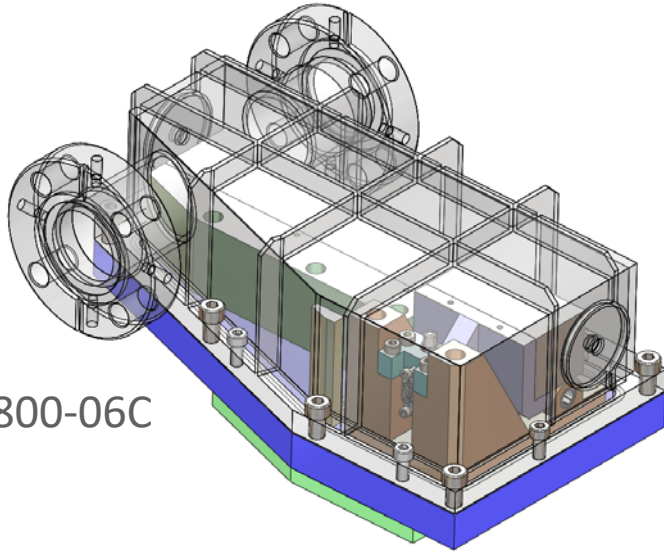
**APS multi-dimensional flexure stage for hard x-ray
KB mirror focusing at sub-50-nanometer scale**
Deming shu et al, ASPE (2014)

Linear stages: step: 20/40 nm; range: +/- 350 um

Tip-tilt stages: step: 20 nrad; range: +/- 5.4 mrad (H), +/- 3.5 mrad (V)

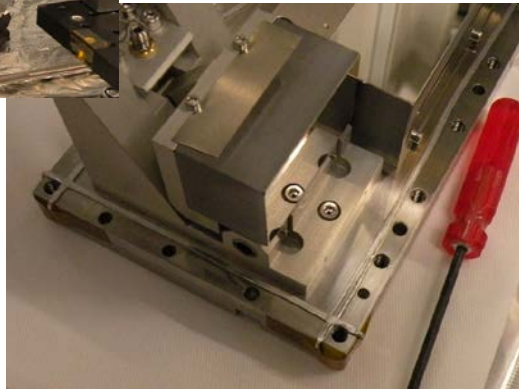


UHV Mirror Box

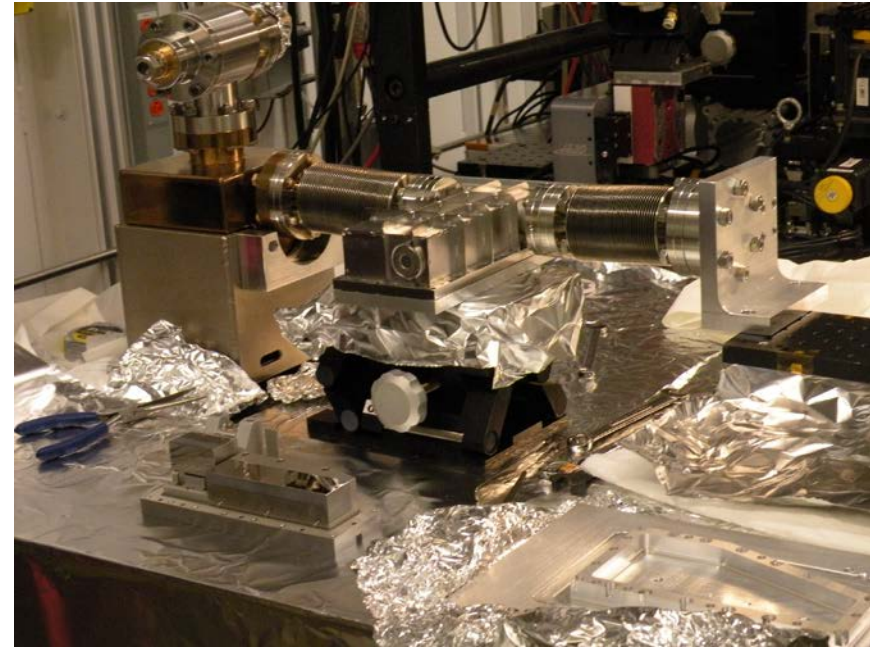


Z8-580800-06C

- Maximizing working distance
Mirror edge to focus: 40 mm;
Special Be window design.
- Box strength: barometric pressure change; Vacuum force balance.
mirror angular stability
- UHV challenge: gasket seal
- **Consider the Weather! (~10%)**



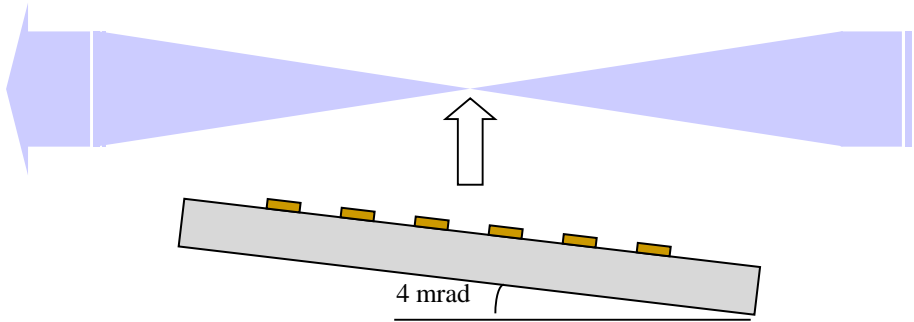
Gasket seal:
Ag foil;
Al wire;
O-ring.



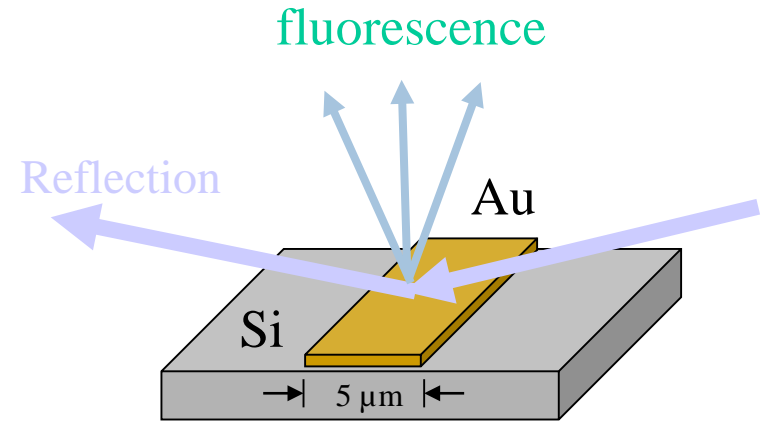
UHV achieved: 1×10^{-8} torr.
Stable for 8 months already!



Measurement of focal size

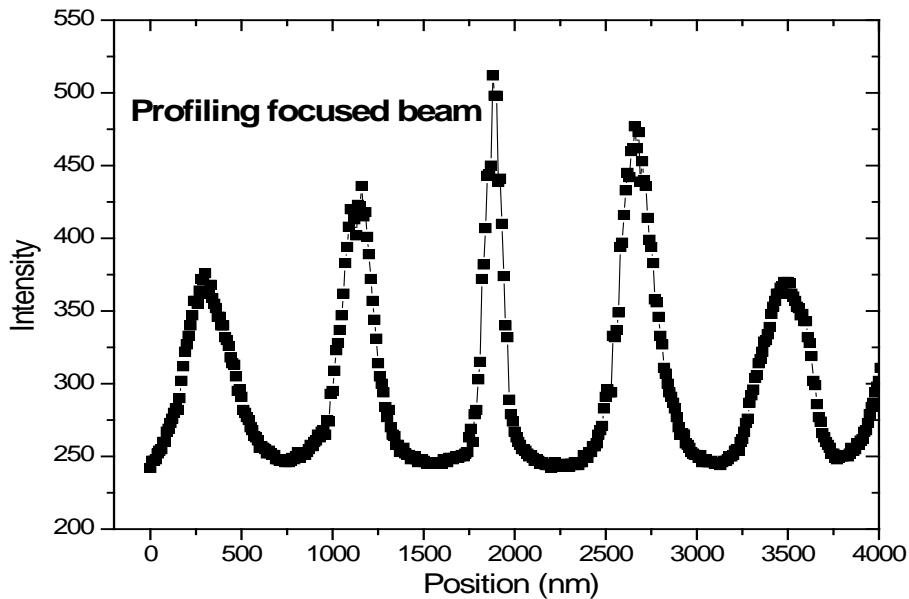


Nano-slit array

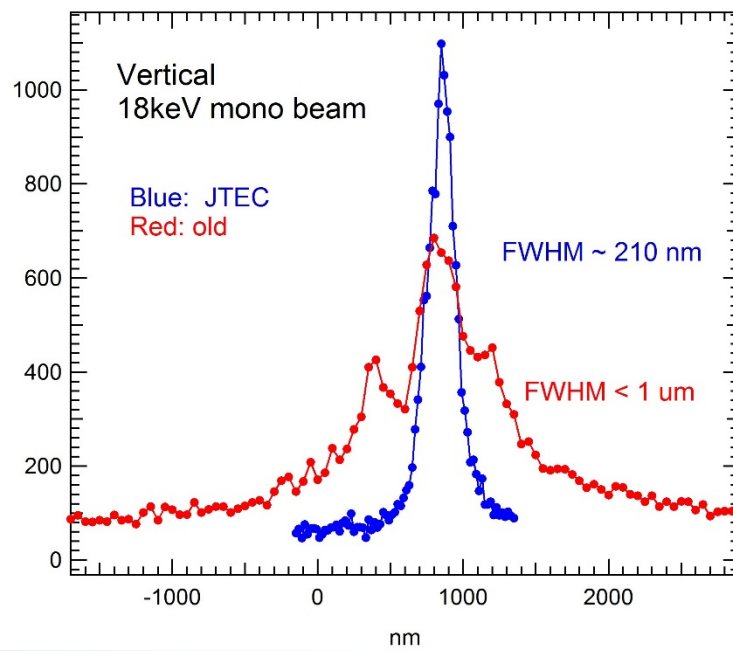
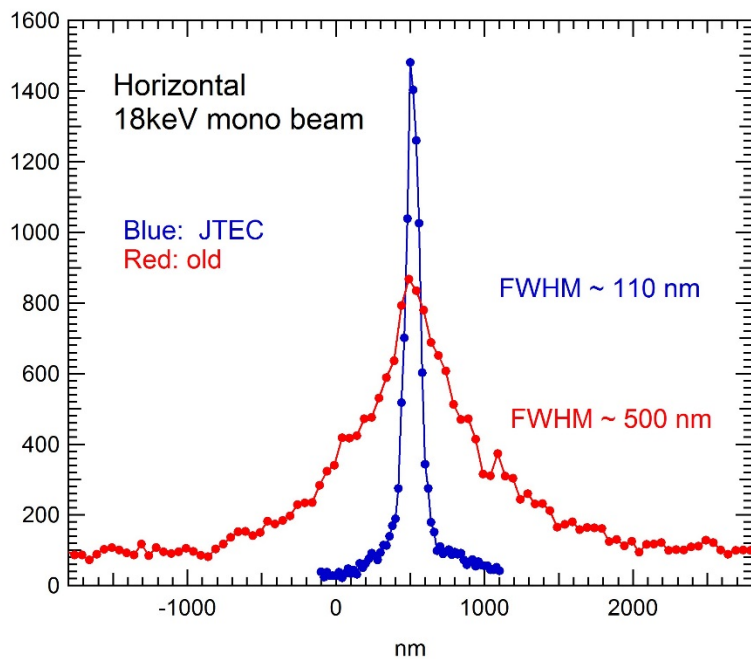
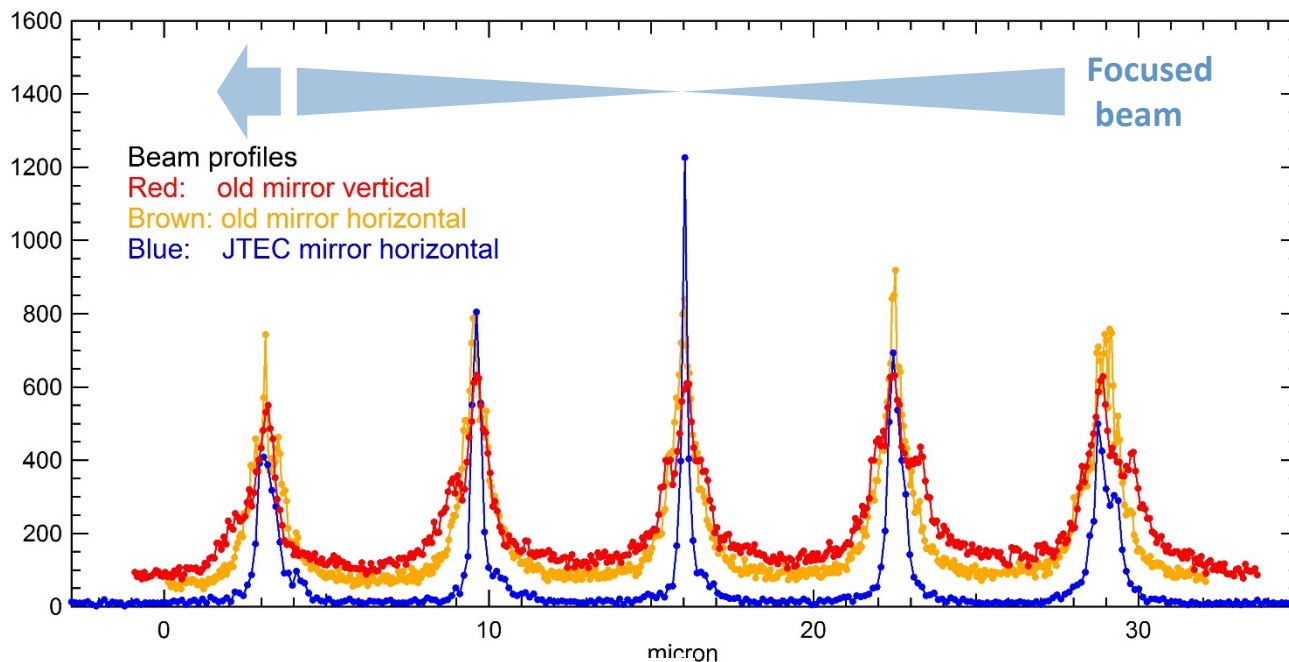


A 5 μm wide gold film stripe at grazing angle is equivalent to a 20 nm wide slit

Nano-slit/reflector



JTEC mirror focusing at 34-ID-E

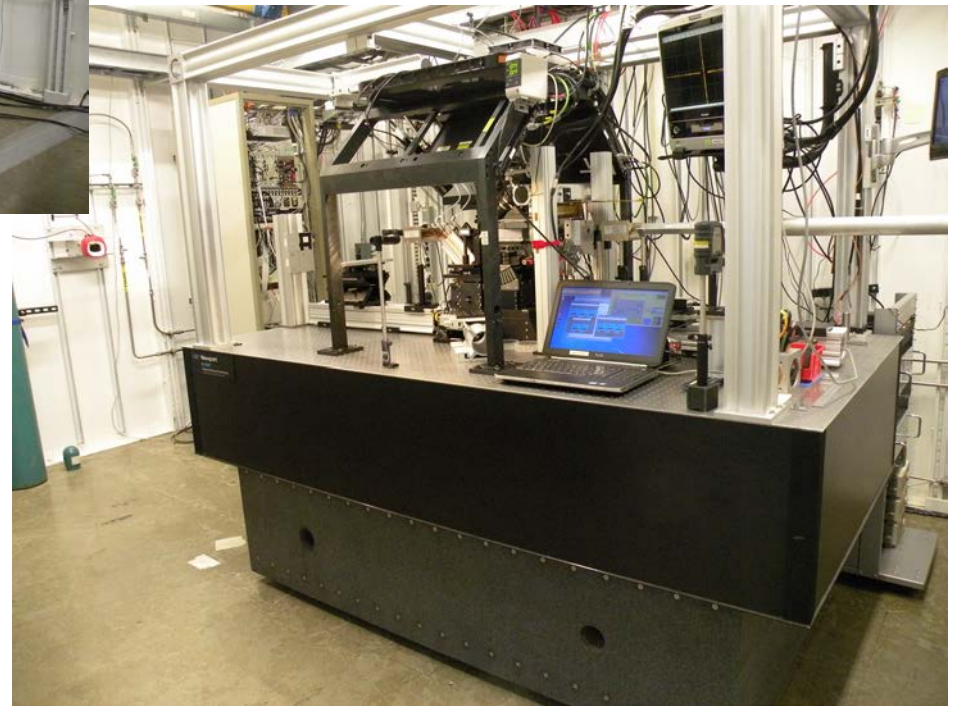


Beam stability Improvement for User Operation



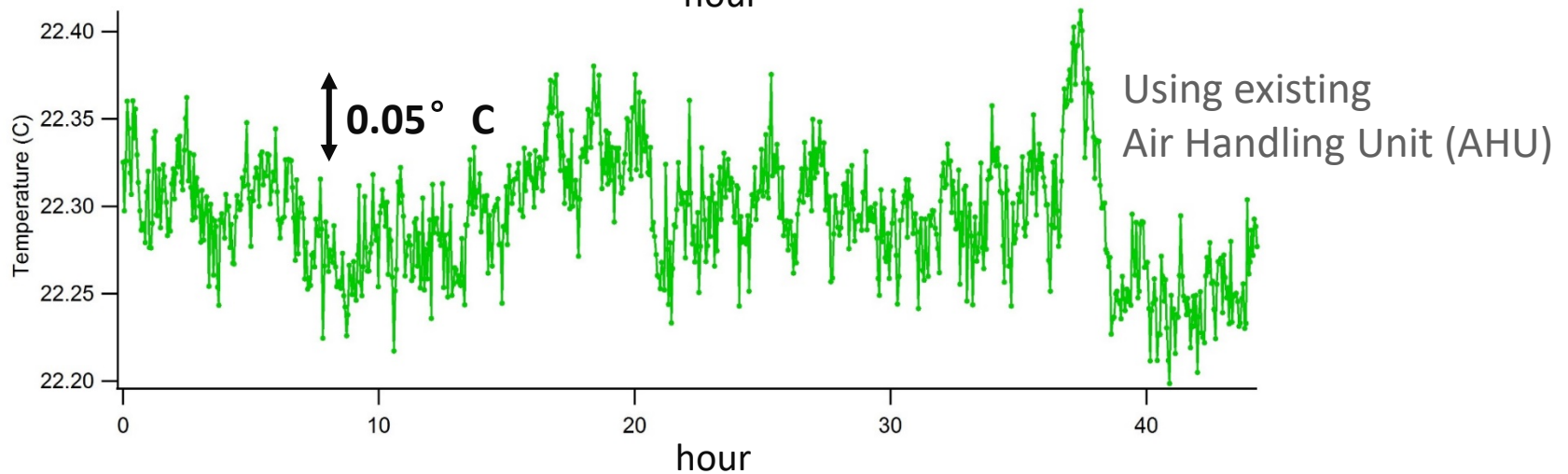
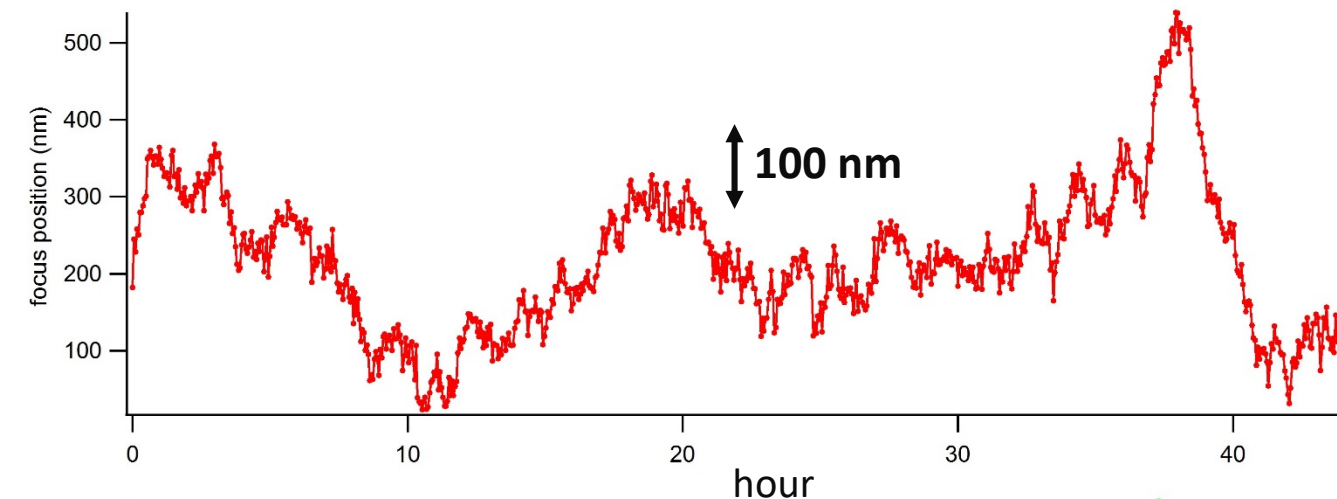
2001 – 2016

**Rms vibrations were ~70 nm vert. &
100 nm horiz.**



2017 – vibrations down to 40 nm

Beam stability ...



- Temperature stability of the hutch/table needs to be improved!
- **Beamline is not ready for operating at sub-100 nm level.**



Requirements with MBA

48 Bunch	source FWHM	demag at 62 m	focus with 0.1 μ r rms	Diffraction limit
Horiz.	43.6 μ m	886 (fl =70 mm)	52 nm	52
Vert.	26.9	436 (fl =142 mm)	67.8	42
324 Bunch				
Horiz.	51 μ m	886	59.2	
Vert.	13	436	41.1	
48 Bunch	source FWHM	demag at 66 m	focus with 0.05 μ r rms	Diffraction limit
Horiz.	43.6 μ m	1200 (fl =55 mm)	36.7 nm	41
Vert.	26.9	550 (fl =120 mm)	50.4	37
324 Bunch				
Horiz.	51 μ m	1200	42.8	
Vert.	13	550	26.5	

- Vibrations must be order of slope error
 - < 100nr for large spot
 - < 50 nr for small spot
- Current sample stage resolution is 50 nm with minimum step size of 20 nm.
- MBA, Positioners must be better than the spot size.
 - at 50 nm, need 10 nm positioning and stability.
 - To do coherent scattering must be < diffraction limit, <40 nm.

